

AMENDMENTS TO THE CLAIMS

The following listing of claims will replace all prior versions and listings of claims in the application.

LISTING OF CLAIMS

1. – 2. (Cancelled).
3. (Currently Amended) A mask vapor deposition system comprising:
 - an electrostatic chucking mechanism for attracting a subject for deposition using electrostatic attraction;
 - a deposition mask, brought into close contact with a face of the deposition subject, for depositing a deposition material in a predetermined pattern, the face being reverse to that of the deposition subject attracted by the electrostatic chucking mechanism, the mask being made of silicon;
 - an evaporation source for evaporating the deposition material; and
 - a vacuum chamber,wherein the mechanism, mask, and source are at least placed in the vacuum chamber.
4. (Cancelled).
5. (Currently Amended) A mask vapor deposition system comprising:
 - a deposition mask for attracting a subject for deposition using electrostatic attraction and depositing a deposition material on the deposition subject in a predetermined pattern, the mask being made of silicon and having positive and negative electrodes thereon;
 - an evaporation source for evaporating the deposition material; and

a vacuum chamber,

wherein the mask and source are at least placed in the vacuum chamber.

6. – 12. (Cancelled).

13. (Currently Amended) An apparatus for manufacturing a display panel, comprising:

an electrostatic chucking mechanism for attracting a glass substrate that is a subject for deposition using electrostatic attraction;

a deposition mask to be brought into close contact with a face of the glass substrate in order to deposit an organic material, which is used for forming electroluminescent elements on the glass substrate in a predetermined pattern, the face being reverse to that of the glass substrate attracted by the electrostatic chucking mechanism, the mask being made of silicon;

an evaporation source for evaporating the organic material; and

a vacuum chamber,

wherein the mechanism, mask, and source are at least placed in the vacuum chamber.

14. – 15. (Cancelled).